



501.30598CC3

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): MORIOKA, et al

Serial No.: 09/805,188

Filed: March 14, 2001

For: METHOD AND APPARATUS FOR ANALYZING THE STATE OF  
GENERATION OF FOREIGN PARTICLES IN  
SEMICONDUCTOR FABRICATION PROCESS

Group: 2877

Examiner: T. Nguyen

*f/Elite*  
*B*  
*G. S. Galy*  
*6-18-02*

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AMENDMENT

Commissioner for Patents  
Washington, D.C. 20231

June 7, 2002

Sir:

The following amendments and remarks are respectfully  
submitted in connection with the above-identified application  
in response to the Office Action dated April 8, 2002.

IN THE CLAIMS:

Please add the following new claims:

--26. A processing method according to claim 1, further  
comprising controlling an operation of the semiconductor  
fabrication line in accordance with the data foreign particle  
defects detected.

*B!*

27. A processing method according to claim 1, further  
comprising obtaining information of distribution of foreign  
particle defects on the substrate and storing the obtained